

10/07/02
02/13/02
JCS/579

U.S. UTILITY Patent Application

PATENT NUMBER and
ISSUE DATE

APPL NUM 10073223	FILING DATE 02/13/2002	CLASS 430	SUBCLASS 270.1	CAU 1752	EXAMINER Lee, J-J
**APPLICANTS: Nishi Tsunehiro; Nakashima Mutsuo; Tachibana Seiichiro; Funatsu Kenji;					
**CONTINUING DATA VERIFIED:					
BEST AVAILABLE COPY					
** FOREIGN APPLICATIONS VERIFIED: JAPAN 2001-037247 02/14/2001 JAPAN 2001-037262 02/14/2001 JAPAN 2001-037271 02/14/2001					
PG-PUB <input type="checkbox"/> DO NOT PUBLISH <input type="checkbox"/>		RESCIND <input type="checkbox"/>			
Foreign priority claimed <input type="checkbox"/> yes <input type="checkbox"/> no		ATTORNEY DOCKET NO			
35 USC 119 conditions met <input type="checkbox"/> yes <input type="checkbox"/> no		KOJIM-446			
Verified and Acknowledged Examiners's initials					
TITLE : Polymer, resist composition and patterning process					
<small>U.S. DEPT. OF COMM./PAT. & TM.-PTO-435L (Rev. 12-94)</small>					

NOTICE OF ALLOWANCE MAILED		Assistant Examiner		CLAIMS ALLOWED	
				Total Claims	Print Claim for O.G.
ISSUE FEE		Primary Examiner	DRAWING		
Amount Due	Date Paid		Sheets Drwg.	Figs. Drwg.	Print Fig.
<input type="checkbox"/> TERMINAL DISCLAIMER		PREPARED FOR ISSUE	Applicant Examiner		
WARNING: The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368, Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.					

FILED WITH:

☐ DISK (CRF)

☐ CD-ROM
(Attached in pocket on right inside flap)